

1 **ABSTRACT OF THE DISCLOSURE**

2 This invention is a method for cleaning a semiconductor
3 manufacturing system, which passes a highly volatile liquid agent through the
4 system to remove the impurities and to dissolve chemicals used in the system.
5 The cleaning agent dissolves and washes the chemicals out of the system to
6 keep the chemicals from combining with moisture in the air and forming oxide
7 particles. By washing with a liquid, residual gases and impurities in the system
8 are rapidly removed from the system. After washing the system, the cleaning
9 agent is quickly dried because the cleaning agent is highly volatile. Thereby,
10 the system is cleaned efficiently within a short time by using this method.